

In the Claims:

1. (Original) A method for use in fabricating a chip, the method comprising the steps of:  
determining a density and location of at least one functional area of a layer; and  
adding dummy structures to said layer as a function of the determined density and  
determined location.
2. (Original) The method of claim 1 wherein for at least one of the dummy structures, the  
adding step includes the steps of:  
determining a placement of said one dummy structure as a function of the width and  
density of functional areas within a predetermined distance of a location; and  
determining a size of said one dummy structure as a function of the determined  
placement.
3. (Original) The method of claim 2 further comprising determining a shape of said one  
dummy structure as a function of the determined size.
4. (Original) A method for use in fabricating a chip, the method comprising the steps of:  
determining a density and location of functional areas of a layer in relation to a location  
being processed; and  
adding dummy structures to said layer as a function of the determined density and  
determined location, said dummy structures each having placement determined as a function of  
the width and density of the functional areas, size determined as a function of the determined  
placement, and shape determined as a function of the determined size.